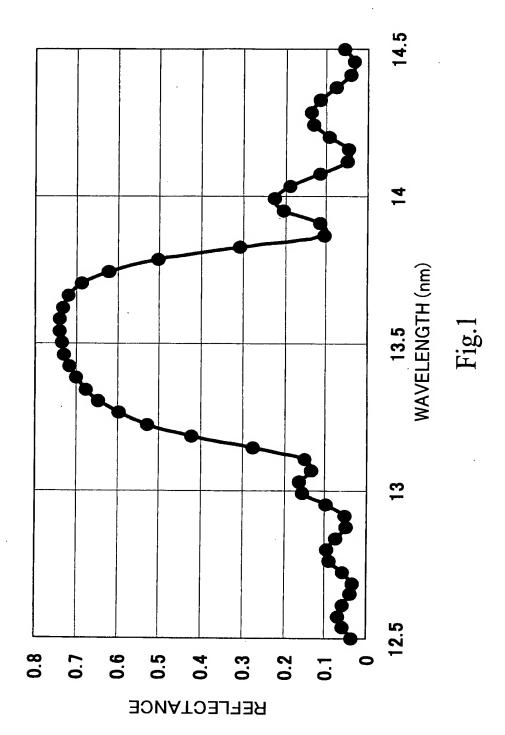
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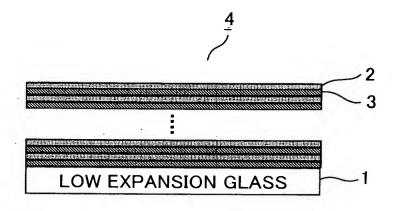


Fig.2

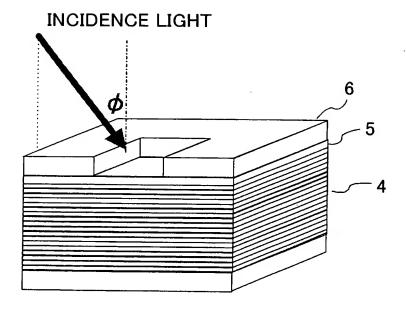
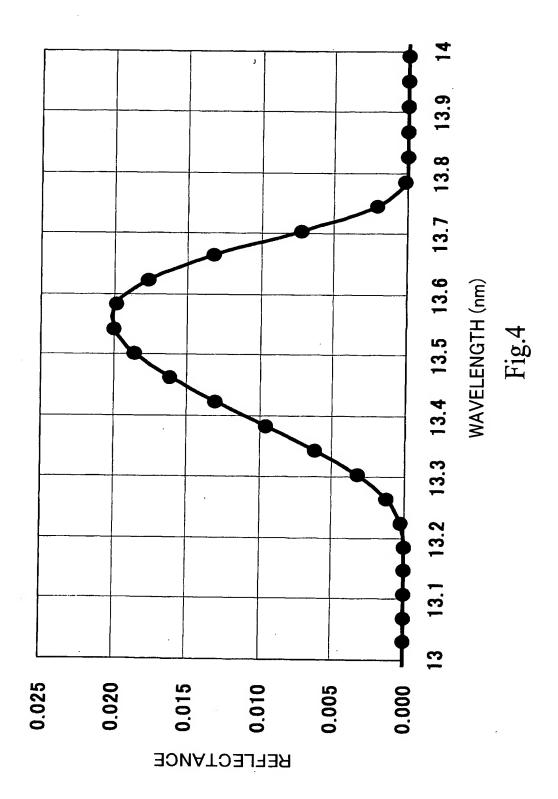
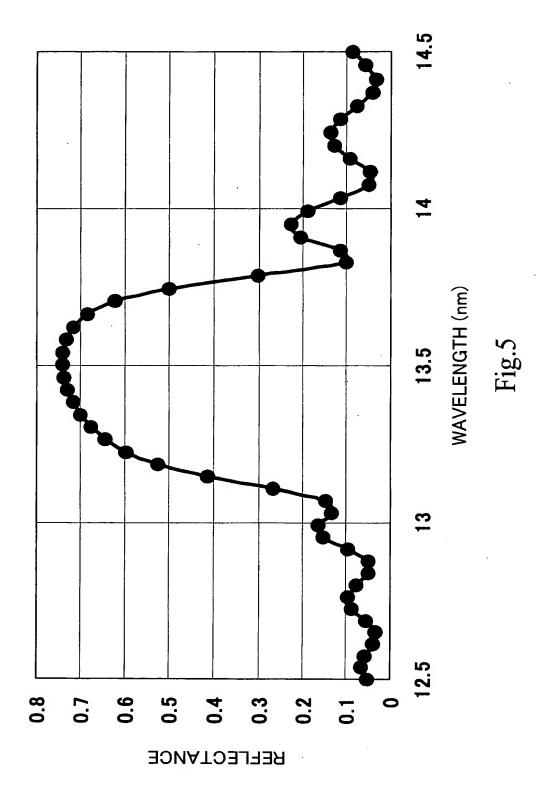
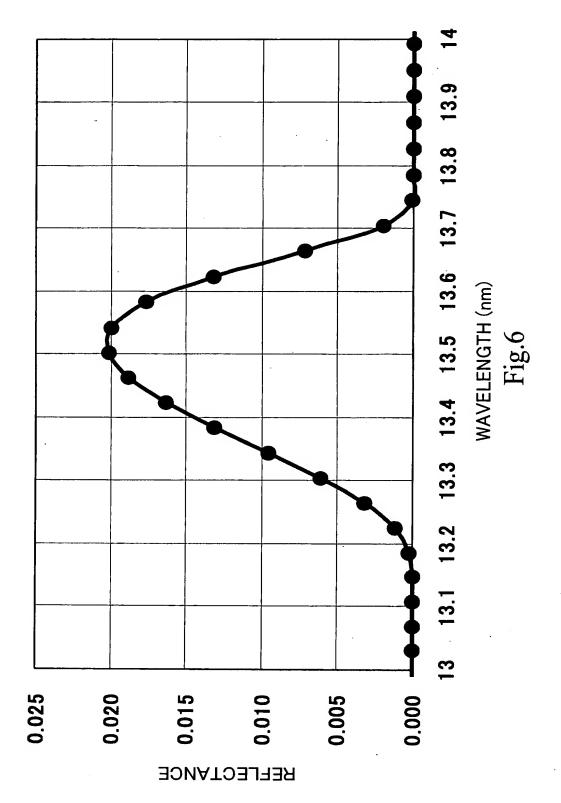


Fig.3







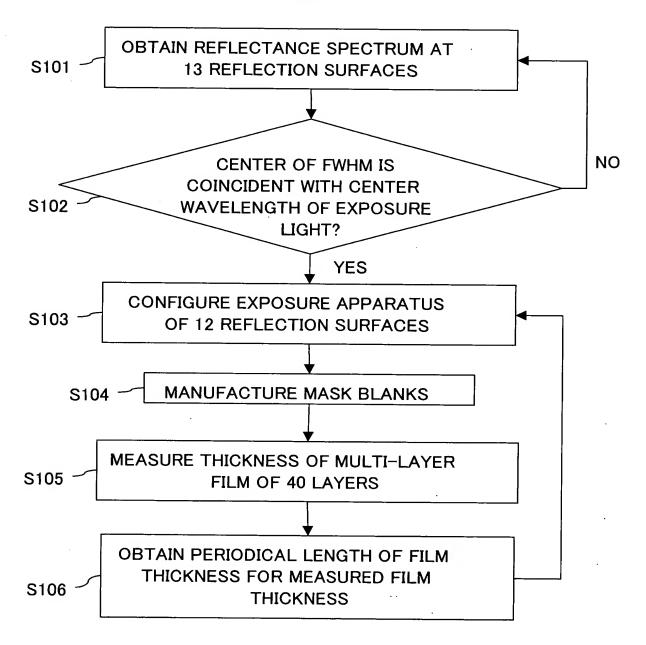


Fig.7

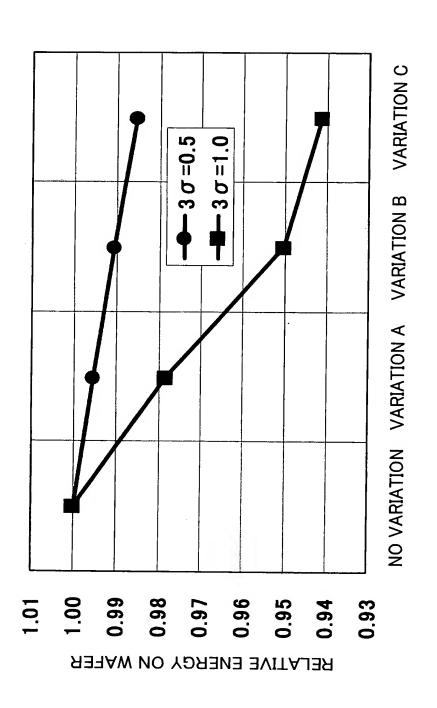
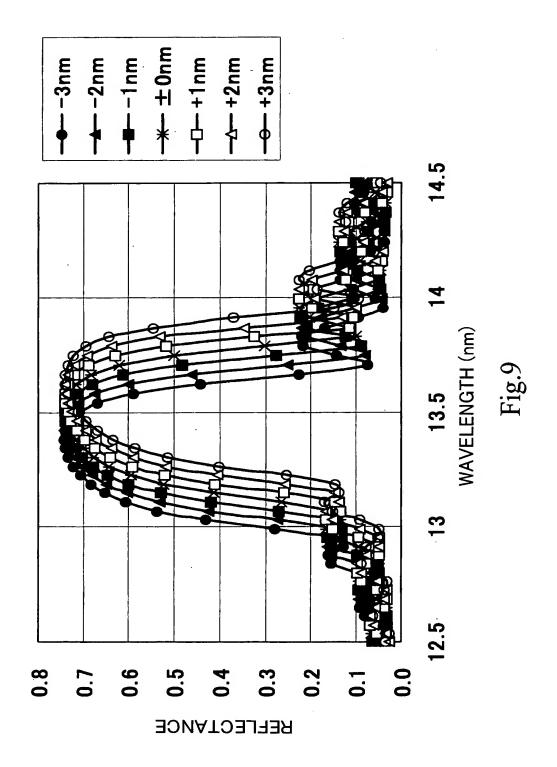
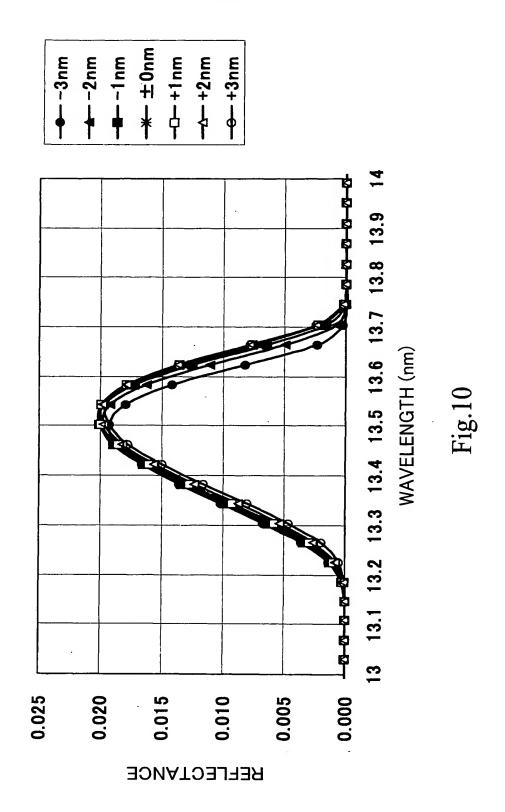
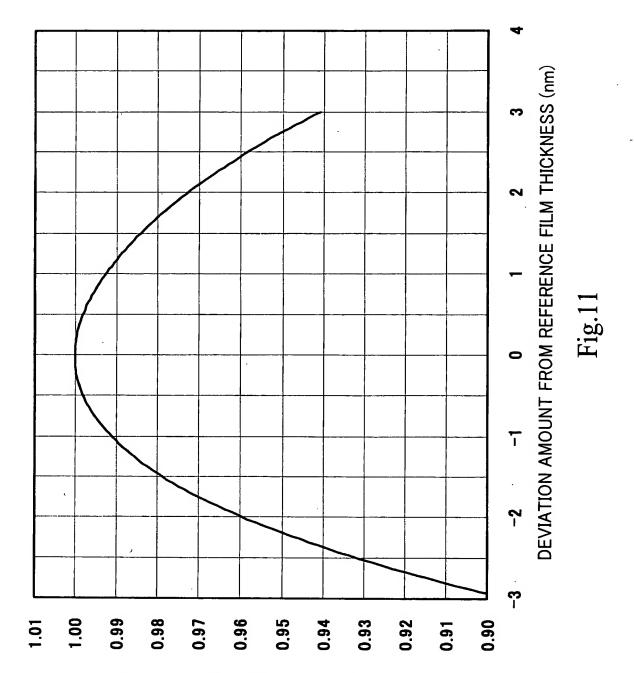


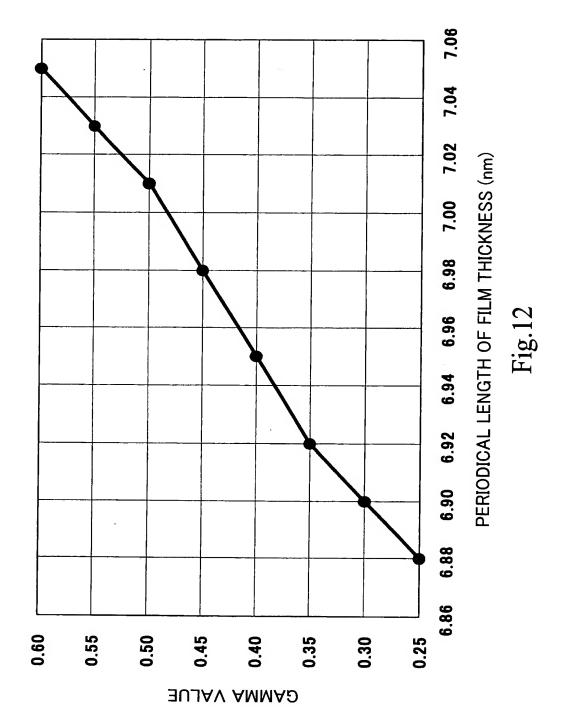
Fig.8

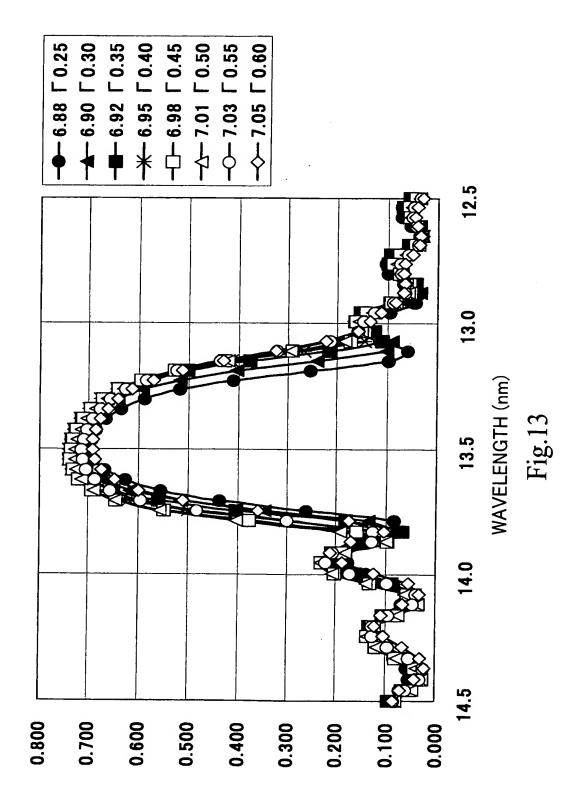


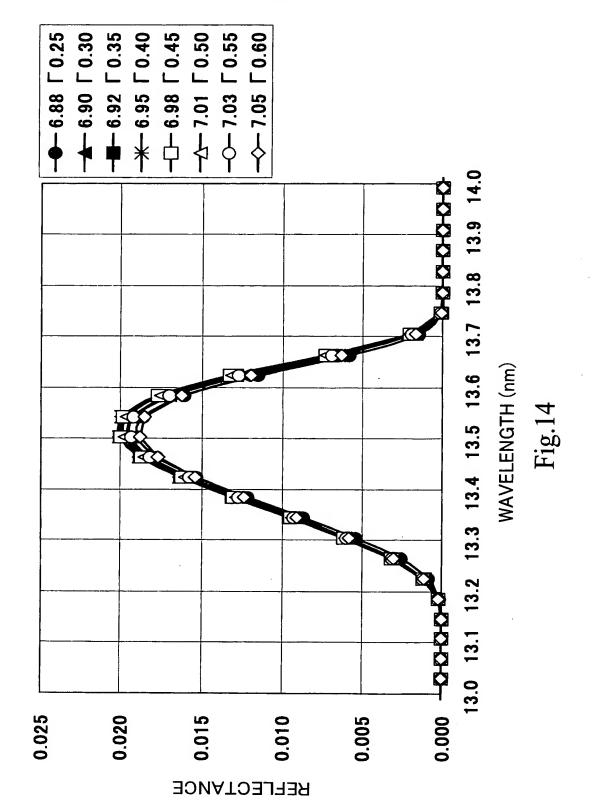


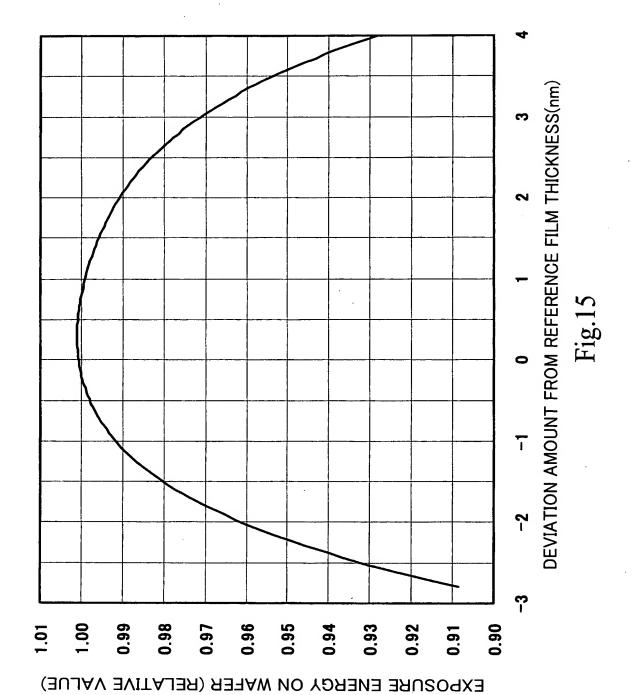


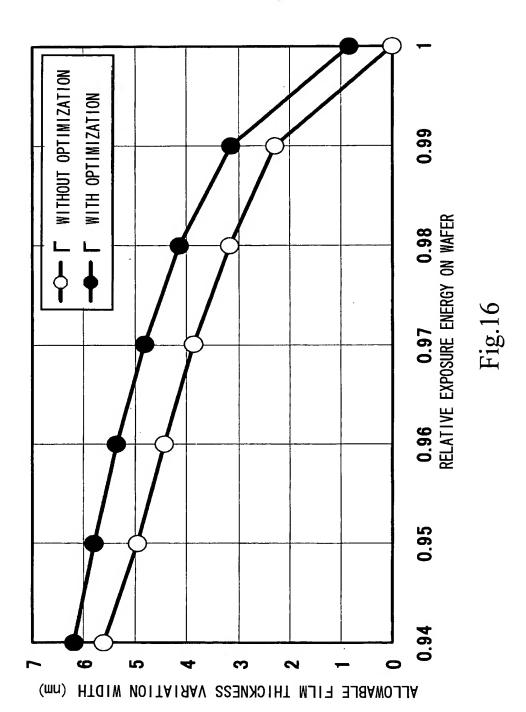
EXPOSURE ENERGY ON WAFER (RELATIVE VALUE)

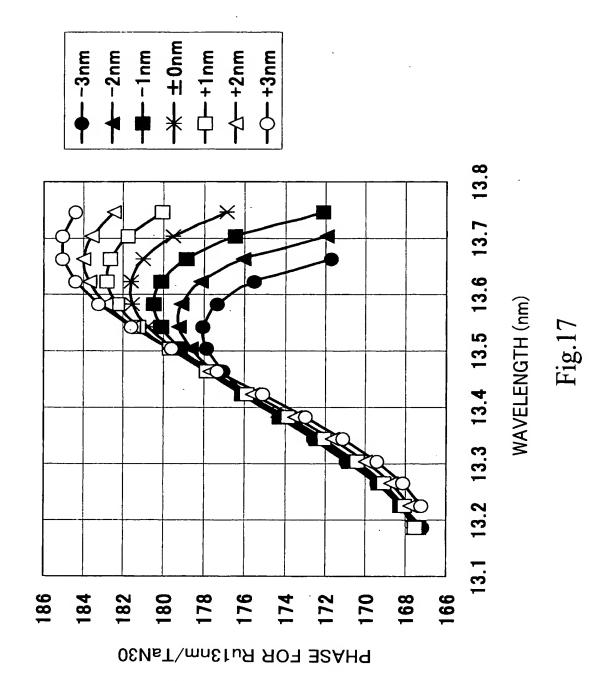


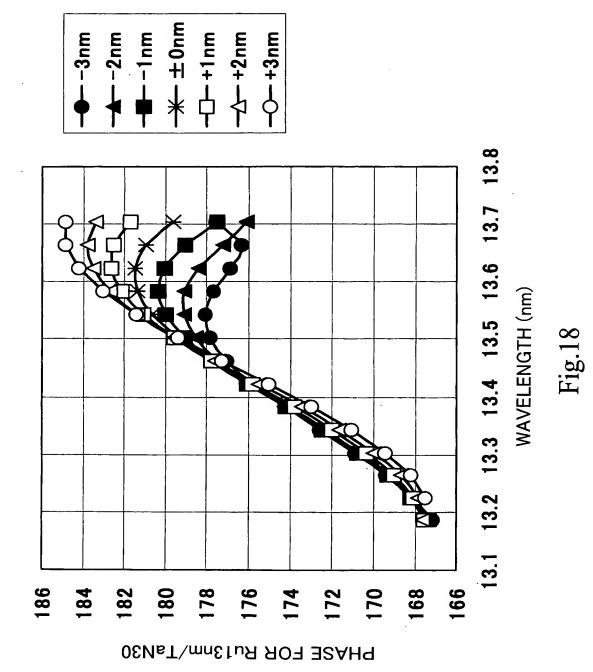


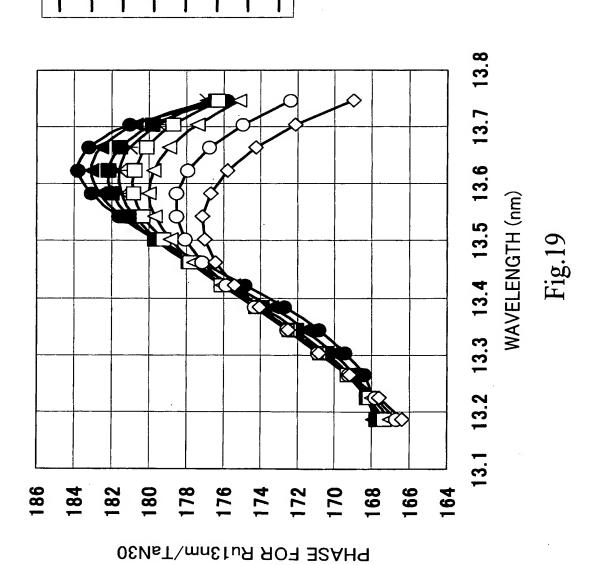


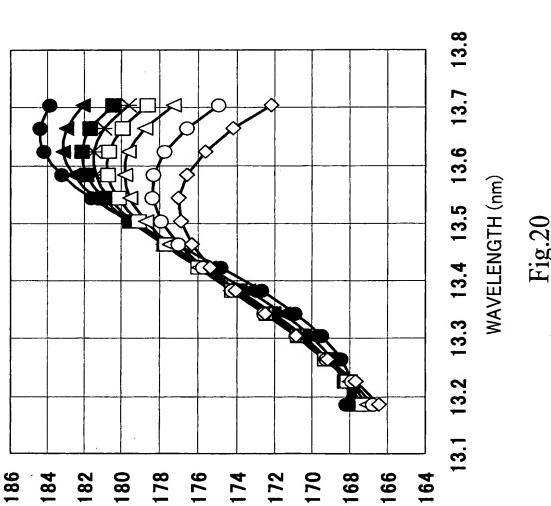






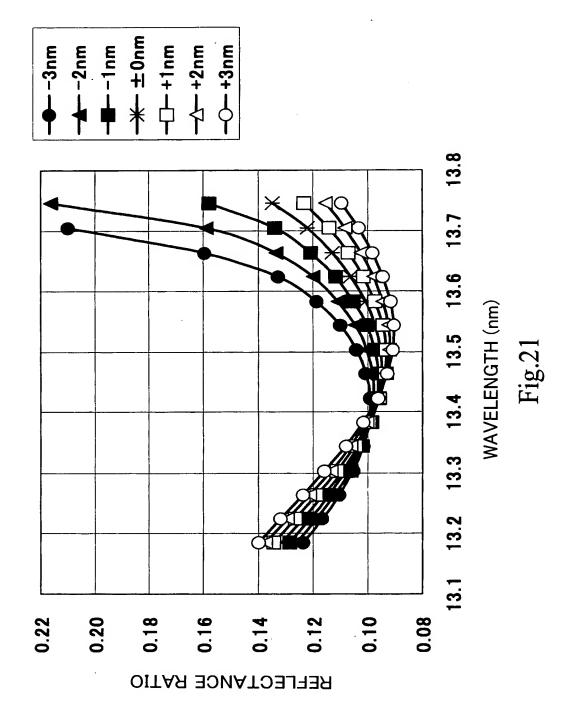


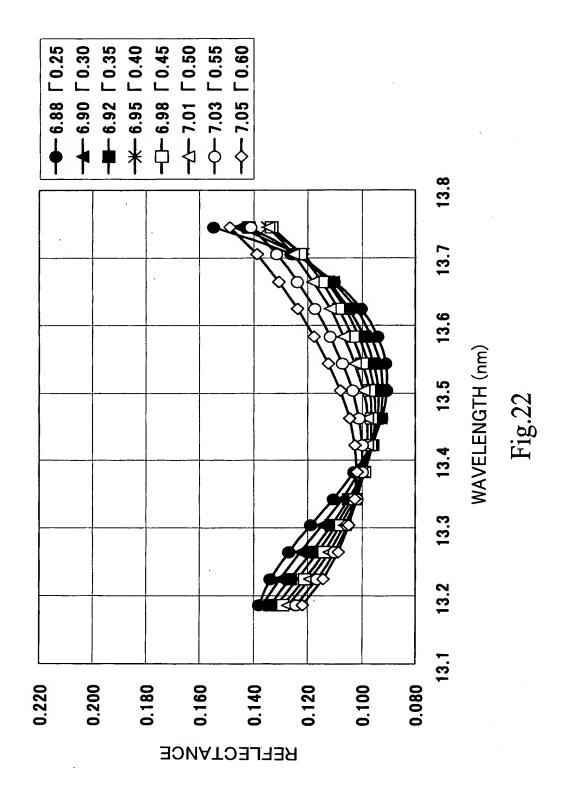




PHASE FOR Ru13nm/TaN30

| + -2.8 | + -1.2 | + -1.2 | -1.2 | -2.4 | -3.2 | -4 + -4





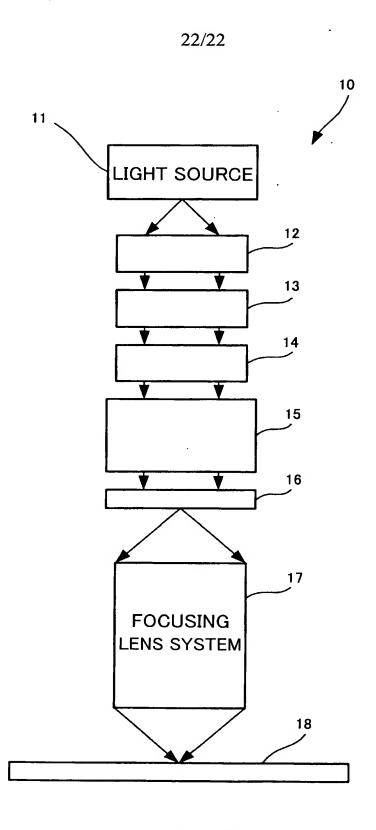


Fig.23